ATTORNEY DOCKET NO. 351913-992432

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Form PTO-14 (modified 2/91)	U.S. DEPT. OF COMMERCE	Attorney Docket Number:	Serial Number:
(modified 2/91)	Patent and Trademark Office	2102397-992432	10/762,807
INFORMATION DISCLOS	SURE CITATION		
(Use several sheets if necess	ary)		
		Applicants: Levi, et al.	
		Filing date: January 21, 2004	Group art unit: 2818

U.S. PATENT DOCUMENTS

Examiner Initial	Patent number	Date	Name	Class	Sub- class	Filing date if appropriate
a	5,911,110	06-1999	Yu et al			·
CL	6,025,270	02-2000	Yoo et al			
<u> </u>						

FOREIGN PATENT DOCUMENTS

	Document number	Date	Country	Class	Sub- class	Translation YES	NO
CL	0 855 739 A1	07-1998	EP			X	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

	Andre et al, "Plasma Etch-Back Planarization Coupled To Chemical Mechanical Polishing For Sub 0.18 um Shallow Trench Isolation Technology," Journal of Vacuum Science And Technology A, Vol. 18, No. 4, pp. 1313-1320, July 2000.
CL	European Search Report corresponding to the related EP Patent Application No. 03256830.5 mailed on August 4, 2005.

Examiner: Calvulu	Date Considered: 9.5.05
EXAMINER: Initial if citation considered, whether or not citation	is in conformance with MPEP '609; Draw line through citation
if not in conformance and not considered. Include copy of this for	m with next communication to the applicant.



INFORMATION DISCLOSURE STATEMENT

Applicants:	Levi, et al.
Application No.	10/762,807
Filed:	January 21, 2004
For:	Method of CMP Planarizing Wafer Topolog
Group Art Unit:	2818
Examiner:	Calvin Lee
Attorney Docket No.:	351913-992432

Commissioner of Patents and Trademarks P.O. Box 1450					
Alexandria, VA 22313-1450					
Dear Sir:					
In accordance with the provisions of 37 C.F.R. § 1.56(a) and 37 C.F.R. § 1.97, Applicant(s) hereby make of record the references listed on the accompanying Form PTO-1449 for consideration by the Examiner in connection with the examination of the above-identified patent application.					
This Information Disclosure Statement:					
(a) accompanies a new patent application submitted herewith.					
(b) is filed within three (3) months of the Filing Date or before the mailing date of a First Office Action on the merits; OR					
(c) after the period defined in (b) but before the mailing date of a Final Rejection or Notice of Allowance, OR					
is filed after the first Office Action and more than three months after the application's filing date or PCT national stage date of entry filing but, as far as is known to the undersigned prior to the mailing date of either a final rejection or a notice of allowance, and is accompanied by either the fee (\$180) set forth in 37 CFR § 1.17(p) or a certification as specified in 37 CFR § 1.97(e), as checked below OR					
(e) is filed after the mailing date of either a final rejection or a notice of allowance, and the issue fee has not been paid, and is accompanied by the requisite petition fee (\$130) set forth in 37 CFR § 1.17(I)(1) and a certification as specified in 37 CFR § 1.97(e), as checked below. This document is to be considered as a petition requesting consideration of the information disclosure statement.					
•					
As required under § 1.97(e), Applicants, through the undersigned, hereby state either that [check the appropriate space]:					
(f)					
(g) No item of information contained in the Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart foreign application, and, to the knowledge of the person signing this Statement after making reasonable inquiry, no item of information contained in the Information Disclosure Statement was known to any individual designated in § 1.56(c) more than three months prior to the filing of the Information Disclosure Statement. It is respectfully requested that each of the references shown on the attached Form PTO-1449					